	Application No.	Applicant(s)	α
· · · · · · · · · · · · · · · · · · ·	09/753,065	JANG ET AL.	
Notice of Allowability	Examiner	Art Unit	
	Lan Vinh	1765	
The MAILING DATE of this communication app All claims being allowable, PROSECUTION ON THE MERITS IS nerewith (or previously mailed), a Notice of Allowance (PTOL-85 NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT F of the Office or upon petition by the applicant. See 37 CFR 1.31	S (OR REMAINS) CLOSED i) or other appropriate comr RIGHTS. This application is	in this application. If not inc munication will be mailed in	cluded due course. THIS
1. $igtimes$ This communication is responsive to $Amendment$ and ren	marks filed on 12/5/2003.		
2. 🔀 The allowed claim(s) is/are <u>1-8 and 10</u> .			
$3.~igotimes$ $ ext{The drawings filed on } extstyle{29~December 2000}$ are accepted by	y the Examiner.		
4. Acknowledgment is made of a claim for foreign priority of a) All b) Some* c) None of the: 1. Certified copies of the priority documents have 2. Certified copies of the priority documents have 3. Copies of the certified copies of the priority of International Bureau (PCT Rule 17.2(a)). * Certified copies not received: Applicant has THREE MONTHS FROM THE "MAILING DATE noted below. Failure to timely comply will result in ABANDON THIS THREE-MONTH PERIOD IS NOT EXTENDABLE. 5. A SUBSTITUTE OATH OR DECLARATION must be substituted in INFORMAL PATENT APPLICATION (PTO-152) which gives a company of the Notice of Draftspe 1) hereto or 2) to Paper No./Mail Date (b) including changes required by the Notice of Draftspe 1) hereto or 2) to Paper No./Mail Date Identifying indicia such as the application number (see 37 CFR each sheet. Replacement sheet(s) should be labeled as such in 7. DEPOSIT OF and/or INFORMATION about the departached Examiner's comment regarding REQUIREMENT.	we been received. We been received in Application ocuments have been received. We of this communication to family application. We of this application. We have been received. We have the attached Expression of the submitted. The submitted of the submitted. The submitted of the submitted. The submitted of the submitted of the header according to 37 to so it of BIOLOGICAL MARKED.	tion No. 09/753,065 yed in this national stage ap ile a reply complying with the XAMINER'S AMENDMENT or declaration is deficient. iew (PTO-948) attached or in the Office action of the drawings in the front (notice) CFR 1.121(d).	ne requirements or NOTICE OF
attached Examiner 5 comment regarding (12 quintament			
 Attachment(s) 1. ☐ Notice of References Cited (PTO-892) 2. ☐ Notice of Draftperson's Patent Drawing Review (PTO-948) 3. ☐ Information Disclosure Statements (PTO-1449 or PTO/SB Paper No./Mail Date) 6. ☐ Interview Paper N 3/08), 7. ☐ Examine	Informal Patent Application Summary (PTO-413), lo./Mail Date r's Amendment/Comment r's Statement of Reasons fo	

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Allowable Subject Matter

1. Claims 1-8, 10 are allowed.

The following is an examiner's statement of reasons for allowance:

Regarding claims 1, 8, the applicants have presented a persuasive argument (page 6 of the applicant's remarks) that the cited prior art of record fails to disclose or suggest a method for releasing a microstructure comprises the step of performing a vapor etching by controlling a temperature and a pressure to be within the vapor region of a phase equilibrium diagram of water/ removing the silicon oxide of a sacrificial layer by performing a vapor etching using anhydrous HF and alcohol by controlling a temperature and a pressure to be within the vapor region of a phase equilibrium diagram of water, whereby the vapor etching is performed under a total pressure of an etching chamber ranged from about 25 Torr to about 75 Torr and a temperature of a substrate ranged from about 25°C to about 75°C. The closest cited prior art of Grant et al (US 5,439,553) discloses the vapor etching is performed under the partial pressures of HF, Methanol and water ranging from about 1 Torr to above about 100 Torr in an etching chamber and a temperature of a substrate ranged from about 20°C to about 95° C (Fig. 1). As seen in Fig. 1, since the partial pressures of HF is already above 100 Torr, of methanol is about 100 Torr in the etching chamber while the temperature of a substrate ranged from about 20°C to about 95°, one skilled in the art would not have found it obvious to modify Grant partial pressures of HF, Methanol and water to produce the claimed total pressure of about 25 Torr to about 75 Torr and a temperature of a substrate ranged from about 25°C to about 75°C.

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Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Conclusion

2. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Lan Vinh whose telephone number is 571 272 1471. The examiner can normally be reached on M-F 8:30-5:30 PM.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Nadine Norton can be reached on 571 272 1465. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

LV

February 5, 2004